

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:)
SHOJI SHIBA, ET AL.) : Examiner: Anca Eoff
Application No.: 10/577,218) : Group Art Unit: 1795
Filed: April 26, 2006) : Confirmation No.: 3411
For: PHOTORESISTIVE RESIN :
COMPOSITION, METHOD OF)
FORMING LEVEL DIFFERENCE :
PATTERN USING THE)
PHOTORESISTIVE RESIN :
COMPOSITION, AND METHOD)
OF PRODUCING INK JET HEAD : Date: June 22, 2009

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

AMENDMENT

Sir:

a) Introductory Comments:

In response to the Official Action dated March 22, 2009, kindly amend the above-identified application as follows.